



E.B. Gun



Description

Odem Electron Beam Evaporation Systems Come in a dual chamber configuration consisting of the main chamber for housing the two e-beam sources and load lock chamber. This configuration with a gate valve between two chambers may be used as a load lock to keep the e-beam source pockets in vacuum while substrate is loaded and unloaded from the main chamber substrate holder or platen. Co-evaporation capability with rotatable multi-pocket source and wafer holder ability to program compositions or compositional gradients through PC control can be provided.

Specifications / Capabilities

- Sequential or Co-Evaporation up to 8 materials.
- Two E-Guns
- Rotatable Multi-Pocket Source
- Programmable Beam Scan
- 10 KW Switching Power Supply
- Turbomolecular Pump, 10⁻⁷ mBar
- Manual Load/Unload
- Auto Load/Unload with Load Lock
- Crystal Thickness Monitor

Available Materials

Gold (Au); Titanium (Ti); Chrome (Cr); Aluminum (Al); Nickel (Ni); Copper (Cu); Silicon dioxide (SiO₂); Platinum (Pt); Palladium (P); Magnesium (Mg)...

Link

<http://www.odemltd.com/>

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